OIPE JC148
SEP 2 3 2002
PATENT & TRADEMARK OFFICE

FORM PTO-1449 MODIFIED

INFORMATION DISCLOSURE CITATION IN AN APPLICATION

Docket No.: 3099.12US02	Application No.: 10/025,037

APPLICANT: Hevey

FILING DATE: December 19, 2001

GROUP ART UNIT: 1761

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
CE	4,867,986	Sep. 1989	Desai et al.			

EXAMINER SIGNATURE Charesse Evans

DATE CONSIDERED 3/2003

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.

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FORM PTO-1449 MODIFIED

INFORMATION DISCLOSURE CITATION IN AN APPLICATION

Docket No.: 2264.22US02	Application No.: 10/025,037

APPLICANT: Hevey

FILING DATE: December 19, 2001

GROUP ART UNIT: Not Assigned

COPY OF PAPERS ORIGINALLY FILED

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
CE	1,758,937	May 1930	Earp-Thomas			
	3,034,968	May 1962	Johnston			
	3,420,742	Jan. 1969	Farr			
	3,897,307	Jul. 1975	Porubcan et al.			
	4,161,397	Jul. 1979	Bellet et al.			
	4,518,696	May 1985	Gehrman et al.			
	5,480,641	Jan. 1996	Casas-Perez			
	5,587,399	Dec. 1996	Acosta et al.			
	5,656,312	Aug. 1997	Erasmus et al.			
	5,756,088	May 1998	Matsuura et al.			
	5,968,569	Oct. 1999	Cavadini et al.			
	6,117,477	Sep. 2000	Paluch			
	6,146,645	Nov. 2000	Deckers et al.			
	6,149,932	Nov. 2000	Allen			
	6,171,632	Jan. 2001	Lanter et al.			
	6,177,107	Jan. 2001	Watson et al.			
	6,197,288	Mar. 2001	Mankoo			
CE	6,228,418	May 2001	Gluck et al.			

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